

Selective Deposition of HfO₂ Films – Supplemental Figure

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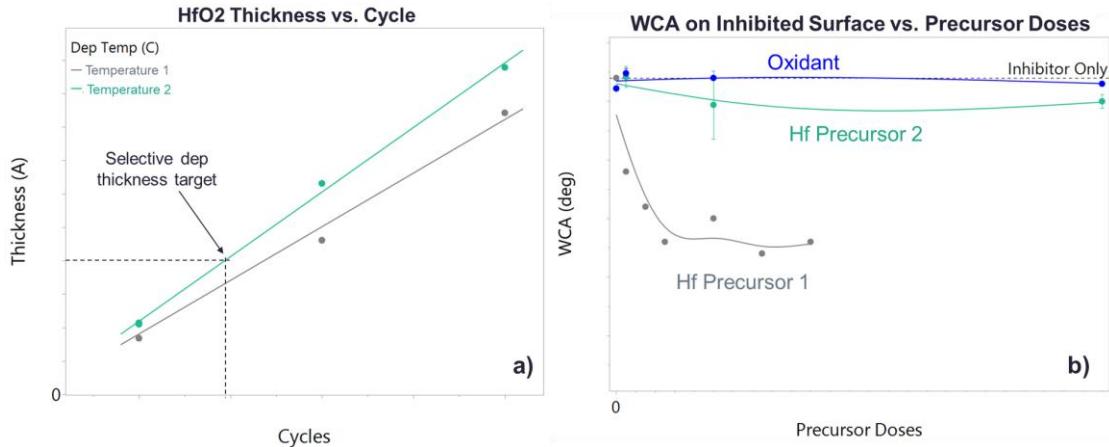


Figure 1: a) HfO₂ thermal ALD deposits linearly as a function of cycle on metal oxide blanket substrates. b) Different Hf precursors break down the inhibitor layer more quickly than others.